

**EUFANET**

*European Failure Analysis Network*



**TOLSA**

Toulouse Open Laboratory for Semiconductor Analysis

**ANADEF**



CENTRE NATIONAL D'ÉTUDES SPATIALES



# **Session 1 : Static Emission microscopy**

**Chairman Christof Brillert, INFINEON Munich**

<b>10:00-10:20</b>	Static Emission microscopy background (Christian Boit, TU Berlin)
<b>10:20-10:40</b>	Use of Static Emission for ESD protection structure analysis (Marise Bafleur, LAAS) (CANCELED)
<b>10:40-11:00</b>	InGaAs versus CCD (Freescale, TOLSA)
<b>11:00-11:20</b>	SIL for improved sensitivity and spatial resolution (Hervé Deslandes, DCGSystems)
<b>11:20-11:40</b>	Best use of SIL: Difference between Aplanatic and Centric SIL, effects of magnification size for the backing objective and the thickness of the Si. (Larry Ross, Semicaps)
<b>11:40-12:00</b>	Influence of Temperature Variation on Electrical and Photon Emission AlGaN/GaN High Mobility Electron Transistors Characterization.( Piotr Laskowski, TU Berlin)
<b>12:00-12:20</b>	Questions and answers (Moderator Bernard Picart, ATMEL Rousset)